

<b>Notice of References Cited</b>	Application/Control No. 10/544,783		Applicant(s)/Patent Under Reexamination TERASHIMA ET AL.	
	Examiner PAPE SENE		Art Unit 4135	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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	C	US-			
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#### NON-PATENT DOCUMENTS

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	V	D. Mangelick et al., "Formation of Ni silicide from Ni(Au) films on (111)Si" April, 15th 1996, Journal of Applied Physics, Vol. 79 Issue 8, Pages 4078-4086.
	W	B. Bokhonov et al., "In-situ investigation of the formation of nickel silicides during interaction of single-crystalline and amorphous silicon with nickel" April, 26 <sup>th</sup> 2001, Journal of Alloys and Compounds, Vol. 319, Pages 187-1195.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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